



Magnetoelectric Interactions in Multiferroic Thin-film Heterosystems and Nanostructures

Hatice Gökdemir

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Contents

1	Introduction	1
2	Theoretical Background	5
2.1	Basic Properties of Ferromagnets	5
2.1.1	Energy Contributions in Ferromagnetic Systems	7
2.1.2	Formation of Magnetic Domains and Domain Walls	9
2.2	Electronic Structure and Magnetism of $\text{La}_{0.7}\text{Sr}_{0.3}\text{MnO}_3$ Films	10
2.3	Ferromagnetism of Thin Fe Films	15
2.4	Basic Properties of Ferroelectrics	16
2.4.1	Structure and Ferroelectric Order of BaTiO_3	16
2.4.2	Ferroelectric Domains and Domain Walls	18
2.5	Interactions across Ferroelectric/Ferromagnetic Interfaces	20
2.5.1	Sample Layouts	22
2.6	Fundamentals of Absorption Spectroscopy	23
2.6.1	X-ray Magnetic Circular Dichroism (XMCD)	25
2.6.2	X-ray Linear Dichroism (XLD)	27
3	Experimental Methods	29
3.1	Sample Growth Techniques	30
3.1.1	Pulsed Laser Deposition (PLD)	30
3.1.2	Electron Beam Evaporation	31
3.2	Magnetic, Structural, and Chemical Pre-characterization Methods	31
3.2.1	SQUID (Superconducting Quantum Interference Device) Magnetometer	31
3.2.2	Atomic Force Microscopy (AFM)	33
3.2.3	X-Ray Diffractometry (XRD)	35
3.2.4	Auger Electron Spectroscopy (AES)	36
3.3	Soft X-Ray Beamline UE56/1-SGM (FZ Jülich Beamline at BESSY-II)	37

CONTENTS

3.3.1	Generation and Basic Properties of Synchrotron Radiation	37
3.3.2	Beamline Instrumentation and Operation Principle	39
3.4	Combined Low Energy Electron and X-ray Photoelectron Emission Microscope (LEEM/XPEEM)	42
3.4.1	Working Principle	43
3.4.2	Low-energy Electron Diffraction (LEED) and μ -LEED	45
3.4.3	Bright Field and Dark Field LEEM	45
3.4.4	Mirror Electron Mode (MEM-LEEM)	46
3.4.5	XPEEM	47
4	Ferromagnetic/Ferroelectric All-Oxide Heterostructures:	
	BTO/LSMO/STO(001)	49
4.1	STO(001) Single Crystal Preparation	49
4.2	LSMO/STO(001)	50
4.2.1	Optimization of LSMO thin films	56
4.3	BTO/LSMO/STO(001)	62
4.4	Effect of oxygen pressure of BTO growth on BTO/LSMO/STO(001)	68
5	Metal/Oxide Artificial Multiferroics:Fe/BTO(001)	79
5.1	BTO(001) Surfaces	79
5.1.1	BTO(001) Single Crystal Cleaning	79
5.1.2	<i>In-situ</i> LEEM and X-PEEM Characterizations of BTO(001) Surfaces	81
5.2	Fe/BTO(001) Interfaces	93
5.2.1	In-situ growth characteristics of Fe on BTO(001)	94
5.2.2	Effect of Fe growth temperature on the electronic structure and crystallinity	101
5.2.3	Elimination of deposition side-effects on the Fe-BTO ferroic domains	104
6	Summary and Outlook	113
	References	117
7	Appendix	135
7.1	Curriculum Vitae	135
7.2	Publications	136
7.3	Conference Contributions	137

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